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Inventor Name Search Result

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Last Name = FUJIEDA

First Name = SHIRO

Application#	Patent#	Status	Date Filed	Title	Inventor Name 4
<u>09996417</u>	Not Issued	030	11/28/2001	IMAGE PROCESSING METHOD AND APPARATUS	FUJIEDA, SHIRO
<u>09974539</u>	Not Issued	030	10/09/2001	CONTOUR INSPECTION METHOD AND APPARATUS	FUJIEDA, SHIRO
<u>09448304</u>	Not Issued	071	12/06/1999	IMAGE PROCESSING APPARATUS AND METHOD, MEDIUM STORING PROGRAM FOR IMAGE PROCESSING, AND INSPECTION APPARATUS	FUJIEDA , SHIRO
<u>07988921</u>	Not Issued	164	03/12/1993	APPARATUS AND METHOD FOR DECIDING OR SETTING IDEAL LIGHTING CONDITIONS AND PHOTOGRAPHIC CONDITIONS, ETC., IN IMAGE PROCESSING SYSTEM, OR FOR AIDING IN DECIDING OR SETTING OF THE LIGHTING CONDITIONS	FUJIEDA , SHIRO

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Electron Device Letters, IEEE , Volume: 20 Issue: 8 , Aug. 1999

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Electronic Components and Technology Conference, 1997. Proceedings., 47th May 1997

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[\[Abstract\]](#) [\[PDF Full-Text \(596 KB\)\]](#) **IEEE CNF****3 Non-volatile FCG (ferroelectric-capacitor and transistor-gate connection) memory cell with non-destructive read-out operation***Kato, Y.; Fujieda, S.; Hayashi, Y.; Kunio, T.;*

VLSI Technology, 1996. Digest of Technical Papers. 1996 Symposium on , 11-15 Oct. 1996

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[\[Abstract\]](#) [\[PDF Full-Text \(164 KB\)\]](#) **IEEE CNF****4 A new encapsulating method for semiconductor devices using resin***Ota, H.; Fujieda, S.; Okuyama, T.; Yoshizumi, A.;*

Electronic Manufacturing Technology Symposium, 1995, Proceedings of 1995 International, 18th IEEE/CPMT International , 4-6 Dec. 1995

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